

AMENDMENTS TO THE SPECIFICATION:

Please replace the paragraph beginning at page 2, line 23, with the following rewritten paragraph:

BRIEF DESCRIPTION OF THE DRAWINGS

The above object and advantages of the present invention will become more apparent by describing in detail exemplary embodiments thereof with reference to the attached drawings in which:

FIG. 1 is a cross-sectional view of a thin film deposition reactor according to the present invention;

FIG. 2 is a perspective view of a lower pumping baffle, an upper pumping baffle, and a chamber insertion shown in FIG. 1;

FIG. 3 is a detailed perspective view of the lower pumping baffle shown in FIG. 2; and

FIG. 4 is a partial perspective view of a stack of the upper pumping baffle and the chamber insertion shown in FIG. 2; and

FIG. 5 is a perspective view of a thin film deposition reactor of FIG. 1.

Please replace the paragraph beginning at page 3, line 6, with the following rewritten paragraph:

FIG. 1 is a cross-sectional view of a thin film deposition reactor according to the present invention, FIG. 2 is a perspective view of a stack of a lower pumping baffle, an upper pumping baffle, and a chamber insertion shown in FIG. 1, FIG. 3 is a detailed perspective view of the lower pumping baffle shown in FIG. 2, and FIG. 4 is a partial perspective view of a stack of the upper pumping baffle and the chamber insertion shown in FIG. 2, and FIG. 5 is a perspective view of a thin film deposition reactor of FIG. 1.